	Application No.	Applicant(s)
Notice of Allowability	10/618,793	TU, KUO-CHI
	Examiner	Art Unit
	David A. Zarneke	2820
	David A. Zameke	2829
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to the election filed 8/4/04.		
2. The allowed claim(s) is/are <u>1-17</u> .		
3. The drawings filed on 15 July 2003 are accepted by the Examiner.		
 4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some* c) None of the: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)). 		
* Certified copies not received:		
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		
5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.		
 6. CORRECTED DRAWINGS (as "replacement sheets") must be submitted. (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of 		
each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).		
7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.		
Attachment(s)	5 Thurston 10	
 Notice of References Cited (PTO-892) Notice of Draftperson's Patent Drawing Review (PTO-948) 	_	atent Application (PTO-152)
	6. ☐ Interview Summary (Paper No./Mail Date	e
3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date 10/22/03	8), 7. Examiner's Amendm	nent/Comment
4. Examiner's Comment Regarding Requirement for Deposit		nt of Reasons for Allowance
of Biological Material	9. Other	

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DETAILED ACTION

Election/Restrictions

The species requirement is hereby removed and all of the method claims, namely claims 1-17, are hereby allowed.

Examiner's Amendment

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows: Cancel claims 18-25.

Reasons For Allowance

The following is an examiner's statement of reasons for allowance: prior art could not be located that taught a method of fabricating an IC device comprising depositing a stress-balancing dielectric layer over a stack of semiconductive materials, depositing an ARC layer thereover, patterning the stack to form first semiconductive devices, and performing thermal processes to form second semiconductive devices wherein the stress-balancing dielectric layer prevents formation of stress-induced voids during the thermal processes.

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While there is prior art that teaches the use of a stress-balancing dielectric layer, see the IDS filed 10/22/03, prior art could not be located that taught using a stress-balancing dielectric layer to prevent the formation of stress-induced voids during the thermal processes. This combination of limitations, in conjunction with the other claim limitations, was neither disclosed in, nor suggested by, the prior art.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to David A. Zarneke whose telephone number is (571)-272-1937. The examiner can normally be reached on M-F 7:30 AM-6 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Tokar can be reached on (571)-272-1812. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

David A. Zarneke Primary Examiner

October 27, 2004